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	APPLICANT HATANO et al.	FILING DATE Concurrently Herewith

U.S. Patent Documents

Foreign Patent Documents

Other Documents (Including Author, Title, Date Pertinent Pages, Etc.)

SDT	C.T. Angelis, C.A. Dimitriadis, M. Miyasaka, F.V. Farmakis, G. Kamarinos, J. Brini and J. Stoemenos, "Effect of Excimer Laser Annealing on the Structural and Electrical Properties of Polycrystalline Silicon Thin-Film Transistors", Journal of Applied Physics (15 October 1999), Vol. 86, No. 8, pp. 4600-4606
SDT	Hiroyuki Kuriyama, Tomoyuki Nohda, Satoshi Ishida, Takashi Kuwahara, Shigeru Noguchi, Seiichi Kiyama, Shinya Tsuda and Shoichi Nakano, "Lateral Grain Growth of Poly-Si Films with a Specific Orientation by an Excimer Laser Annealing Method", Jpn. J. Appl. Phys., Vol. 32 (1993), pp. 6190-6195
SDT	Kenkichi Suzuki, Masakazu Saitou, Michiko Takahashi, Nobuaki Hayashi and Takao Terabayashi, "Correlation Between Power Density Fluctuation and Grain Size Distribution of Laser Annealed Poly-Crystalline Silicon", Part of the SPIE Conference on Laser Applications in Microelectronics and Optoelectronic Manufacturing IV, January 1999, SPIE Vol. 3618, pp. 310-319

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